

LIST OF PUBLICATIONS CITED BY APPLICANT	Atty Docket No. SEL 239	Serial No. 09/782,239
	Applicant Toshimitsu KONUMA et al	
	Filing Date February 13, 2001	Group 2814

U.S. PATENT DOCUMENTS

*EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB- CLASS	FILING DATE
<i>Dae</i>	5,895,228	04/20/99	Biebuyck et al	438	99	03/20/97

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	APPLICANT	English Abstract	English Trans.	FILING DATE
	JP 07-258410	10/09/95	UBE Ind. Ltd.	X		03/18/94
	EP 0 768 352	04/16/97	Hitachi Chem Co.			06/30/95
	EP 0 881 668 A2	12/02/98	Dow Corning Toray Silicone Co. Ltd.			05/27/98
	EP 0 893 485	01/27/99	Sumitomo Chem Co.			07/22/98
	EP 0 899 987	03/03/99	TDK Corp.			08/28/98

OTHER PRIOR ART - NON PATENT LITERATURE DOCUMENTS

(Include name of author (in CAPITAL LETTERS), title of article or item (book, magazine, journal, serial, symposium, catalog, etc.) date, pages(s), volume-issue number(s), publisher, city and/or country where published).

- 1) European Search Report re application no. EP 03 02 0964, mailed December 3, 2003.
- 2) FRITSCH, U. et al, "A Submicron CMOS Two Level Metal Process with Planarization Techniques," V-MIC Conf., June 13-14, 1988 IEEE, pp. 69-75 (1988).
- 3) IBARAKI, N. et al, "A New a-Si TFT with SiO₂/SiN_x Gate Insulator for 10.4 inch LCDs," Proceedings of the International Display Research Conference, IEEE, pp. 97-100, (1991).
- 4) PRAMANIK, D. et al, "A High Reliability Triple Metal Process for High Performance Application Specific Circuits," VLSI Multilevel Interconnection Conference, June 11-12, 1991, pp. 27-33, (1991).

EXAMINER:

Douglas Will

DATE CONSIDERED:

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